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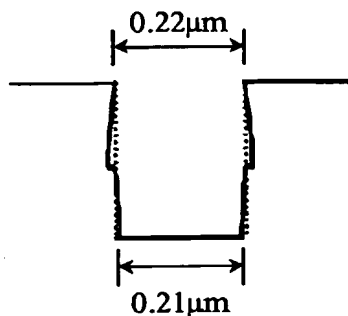
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(54) Title: METHOD AND SYSTEM FOR DYNAMIC MODELING AND RECIPE OPTIMIZATION OF SEMICONDUCTOR ETCH PROCESSES



Desired Result:  
< 100 Å deviation

230

(57) Abstract: A method and system are disclosed for creating dynamic models of etch processes in semiconductor manufacturing. In one embodiment, a method comprises modeling an etch process used in semiconductor manufacturing to generate a dynamic process model. The dynamic process model is used to determine input values that result in a desired output value. A process recipe is optimized for the etch process with the input values.